

**AMENDMENTS TO THE CLAIMS:**

Please amend claim 1, as follows:

**Claim 1 (currently amended):** An electron beam projection mask for ~~arranging use in~~ forming a plurality of high density and low density batch projection regions on a semiconductor substrate so that pattern density may be equalized all over [a] said semiconductor substrate, wherein said high density and low density batch projections are equal in area.

**Claim 2 (original):** An electron beam projection mask according to claim 1, wherein the mask is a stencil type mask.

**Claim 3 (original):** An electron beam projection mask according to claim 1, wherein the mask is a membrane type mask.

**Claim 4 (original):** An electron beam projection mask according to claim 1, wherein the mask is a partial batch electron beam projection mask.

**Claim 5 (original):** An electron beam projection mask according to claim 2, wherein the mask is a partial batch electron beam projection mask.

**Claim 6 (original):** An electron beam projection mask according to claim 3, wherein the mask is a partial batch electron beam projection mask.

**Claim 7 (original):** An electron beam projection mask as claimed in claim 1, wherein the mask is an electron beam projection lithography mask.

**Claim 8 (original):** An electron beam projection mask as claimed in claim 2, wherein the mask is an electron beam projection lithography mask.

**Claim 9 (original):** An electron beam projection mask as claimed in claim 3, wherein the mask is an electron beam projection lithography mask.

HAYES SOLOWAY P.C.  
130 W. CUSHING ST.  
TUCSON, AZ 85701  
TEL 520 882 7623  
FAX 520 882 7643

175 CANAL STREET  
MANCHESTER, NH 03101  
TEL 603 668 1400  
FAX 603 668 8567